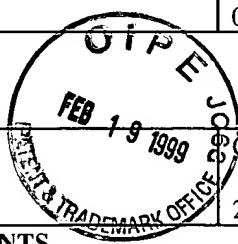


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FORM PTO-1449 US Dept. of Commerce Patent and Trademark Office INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)	ATTORNEY DOCKET NO.	SERIAL NO.
	ATM-337	09/200,495
	APPLICANT	
	Van Buskirk et al	
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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SK		5,783,716	7/21/98	Baum et al	556	136	
SK		5,719,417	2/17/98	Roeder et al	257	295	
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FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)		
SK		Rossnagel, S.M. et al, "Thin high atomic weight refractor film deposition for diffusion barrier, adhesion layer, and seed Layer applications", <i>J. Vac. Sci. Technol. B</i> , Vol. 14, No. 3, May/Jun 1996 pp. 1820-1822
SK		J.L.Vossen, W. Kern, Eds., <i>Thin Film Processes II</i> , Academic Press, Boston, MA, 1991, pp. 763

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EXAMINER	DATE CONSIDERED
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